

Vacuum ▶ PVD Thin films ▶ Leak testing ▶ Plasma



Horizontal industrial metallization system

MIH

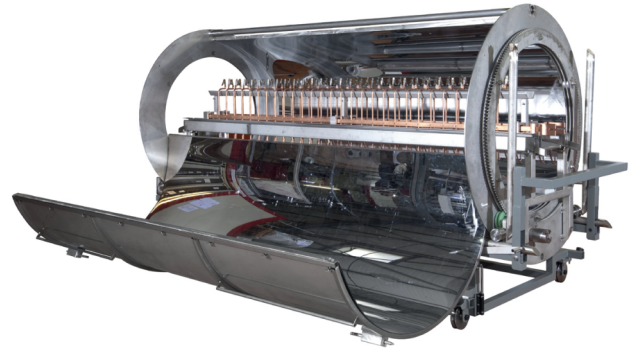


by
allianceconcept

Horizontal industrial metallisation system

Vacuum metallization represents a significant share of thin film deposition applications. Expanding rapidly in recent years it affects areas directly or indirectly connected to public markets. Indeed, in these industries the guideline is to provide a **top quality layer on the largest number of pieces in the shortest time possible**.

We offer three sizes of system to meet your demands. On these projects, the engineering of the pumping package remains a key point for the equipment performances and productivity. Our skilled engineers are at your disposal to answer all your requirements and specifications.



Tools, handling, user-friendly control interface and ergonomics are all critical points to consider to ensure the system ease of use.

Main features

Chamber diameter :	1700, 1900 or 2800 mm
Pre-cleaning :	Glow discharge
System throughput :	Simple or double rotation movement
Cycle time :	<15 min ^[1]
Through the wall installation :	Possible
Fully automatic system controller :	- Process management - Traceability

^[1] These values have been measured on equipment we have delivered and should be handled as information only. The features of a system depend on its final configuration.

